

L Number	Hits	Search Text	DB	Time stamp
-	128	204/224M.ccls. and polish\$3	USPAT	2004/05/25 11:53
-	2	6096652 pn OR 6066030 pn	USPAT	2004/05/25 11:55
-	1	sheer adj stress SAME polish\$3	USPAT	2004/05/25 11:57
-	1	sheer adj stress AND polish\$3 AND processing adj solution	USPAT	2004/05/25 11:58
-	26	sheer adj stress AND polish\$3	USPAT	2004/05/25 12:05
-	16486	sheer adj stress AND polish\$3 AND solution	USPAT	2004/05/25 12:09
-	18545	sheer adj stress AND polish\$3 AND solution	USPAT	2004/05/25 12:09
-	8339	sheer adj stress AND electropolish\$3	USPAT	2004/05/25 12:10
-	8009	sheer adj stress SAME electropolish\$3	USPAT	2004/05/25 12:10
-	0	sheer adj stress SAME electropolish\$3	USPAT	2004/05/25 12:11
-	1	sheer adj stress AND electropolish\$3	USPAT	2004/05/25 12:12
-	0	sheer adj stress AND 156/345 ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 12:29
-	0	sheer adj stress AND 205/8.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/25 12:38
-	364	sheer adj stress	USPAT	2004/05/25 12:39
-	164	sheer adj stress AND solution	USPAT	2004/05/25 12:41
-	13	sheer adj stress AND solution AND polish\$3	USPAT	2004/05/25 12:44
-	364	sheer adj stress	USPAT	2004/05/25 13:15
-	25	sheer adj stress AND jet	USPAT	2004/05/25 13:19
-	0	sheer adj stress AND electrochemical adj polish\$3	USPAT	2004/05/25 13:26
-	89	205/670.ccls.	USPAT	2004/05/25 13:34
-	257	205/670.ccls. electrochemical adj polish\$3	USPAT	2004/05/25 13:43
-	170	205/670.ccls. electrochemical adj polish\$3 AND film	USPAT	2004/05/25 13:44